

3rd Announcement

The 29th Symposium on Photomask and Next Generation Lithography Mask Technology

Photomask Japan 2023 Digital Forum

April 25(Tue.) - 27(Thu.)

Symposium Chair: Prof. Takeo Watanabe, University of Hyogo (Japan)

Organized by Photomask Japan and SPIE

Co-organized by BACUS and EMLC



Program

Latest Program <https://www.photomask-japan.org/program.html>

Keynote Speakers: Kurt Ronse (imec), Seiji Nagahara (Tokyo Electron)

The program is subject to change without notice.

April 25 (Tue.)			April 26 (Wed.)			April 27 (Thu.)		
PDT UTC-7	CEST UTC+2	JST UTC+9	PDT UTC-7	CEST UTC+2	JST UTC+9	PDT UTC-7	CEST UTC+2	JST UTC+9
		Digital Forum			Digital Forum			Digital Forum
		9:00 - 9:10 Opening	25-Apr 17:00	26-Apr 2:00	9:00 - 10:10 Session 6 Opening Session: Day 2	26-Apr 17:00	27-Apr 2:00	9:00 - 10:50 Session 10 Opening Session: Day 3
24-Apr 17:00	25-Apr 2:00	9:10 - 10:30 Session 1 Opening Session: Day 1			Keynote Seiji Nagahara (Tokyo Electron)			Invited Talk Aki Fujimura (D2S)
		Keynote Kurt Ronse (imec)	18:30	3:30	10:10 - 10:30 Break			
18:30	3:30	Invited Talk Matt Hettermann (EUV Tech)						
		10:30 - 10:50 Break	18:30	3:30	10:30 - 12:10 Session 7 Mask Data Handling	18:50	3:50	10:50 - 11:10 Break
18:50	3:50	10:50 - 12:30 Session 2 EUV Inspection & Repair			Invited Talk Masakazu Hamaji (Nippon Control System)	19:10	4:10	11:10 - 12:20 Session 11 Patterning Technologies
		Invited Talk Toshiyuki Todoroki (Lasertec)	20:10	5:10	Abhishek Shendre (D2S)			Invited Talk Yuho Kanaya (Nikon)
20:30	5:30	Sang-Joon Cho (Park Systems)			12:10 - 13:10 Lunch Break	20:20	5:20	12:20 - 13:20 Lunch Break
		12:30 - 13:30 Lunch Break	21:10	6:10	13:10 - 14:50 Session 8 Poster Session [Zoom Breakout rooms]	21:20	6:20	13:20 - 14:50 Panel Discussion Curvilinear Masks - What Should We Do for High Volume Manufacturing?
21:30	6:30	13:30 - 15:00 Session 3 NIL 1			14:50 - 15:10 Break	22:50	7:50	14:50 - 15:10 Break
		Invited Talk Tomohiko Yamaji (Tokyo Electron)	22:50	7:50	15:10 - 15:30 Sponsor Session	23:10	8:10	15:10 - 16:10 Session 12 AI Utilization
23:00	8:00	15:00 - 15:20 Break			15:30 - 15:50 Break			
23:20	8:20	15:20 - 16:50 Session 4 NIL 2	23:10	8:10	15:50 - 17:10 Session 9 EUV Technologies	23:10	8:10	16:10 - 16:30 Break
		Invited Talk Christine Thanner (EV Group)	23:50	8:50	Invited Talk Tatiana Kovalevich (imec)	27-Apr 0:10	9:10	16:30 - 17:40 Session 13 Writing Tools
25-Apr 0:50	9:50	16:50 - 17:10 Break			Klaus Gwosch (Carl Zeiss)	0:30	9:30	Invited Talk Annette Schnettelker (IMS Nanofabrication)
1:10	10:10	17:10 - 18:40 Session 5 EUV Lithography & Source	26-Apr 1:10	10:10		1:50	10:50	17:40 - 17:50 Closing
		Invited Talk Jan van Schoot (ASML)						
2:40	11:40							

Sponsor Session April 26(Wed.) 15:10-15:30 JST
Mycronic Technologies Corporation

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For registration details, please see <https://www.photomask-japan.org/registration.html>